

Patent Abstracts of Japan

PUBLICATION NUMBER : 08134651
PUBLICATION DATE : 28-05-96

APPLICATION DATE : 11-11-94
APPLICATION NUMBER : 06277449

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INT.CL. : C23C 16/44 H01L 21/3065

TITLE : GAS FOR PLASMA CVM

ABSTRACT : PURPOSE: To solve the problems of a low machining speed and low efficiency of utilization of gas of using gas for machining selected from among F_2 , interhalogen compds. and nitrogen fluorides.

CONSTITUTION: This gas for plasma CVM(Chemical Vaporization Machining) is one kind of gas or a mixture of two or more kinds of gases selected from among F_2 , interhalogen compds. and nitrogen fluorides. The interhalogen compds. are ClF , ClF_3 , ClF_5 , BrB , BrB_3 , BrF_5 and BrF_7 . The nitrogen fluorides are NF_3 , N_2F_4 , N_2F_2 and N_3F . Contamination by the deposition of sulfur or its compd. and carbon or it compd. from the surfaces of a body to be machined and an electrode material can be prevented.

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